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Muller et al.

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[54]	ETCH PROFILE SHAPING THROUGH	
	WAFER TEMPERATURE CONTROL	

[75] Inventors: Karl P. Muller; Klaus B. Roithner, both of Wappingers Falls; Bernhard Poschenrieder, Poughkeepsie; Toru Watanabe, Hopwell Junction, all of N.Y.

[73] Assignees: International Business Machines Corporation, Armonk, N.Y.; Siemens Aktiengesellshaft, Munich, Germany; Kabushiki Kaisha Toshiba, Tokyo, Japan

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[52]	U.S. Cl
	156/657.1; 156/651.1; 216/67; 216/37
	216/80
[58]	Field of Search
	156/659.11, 651.1, 662.1, 345 P; 216/2
	41, 67, 37, 80; 204/192.32, 192.37, 298.31

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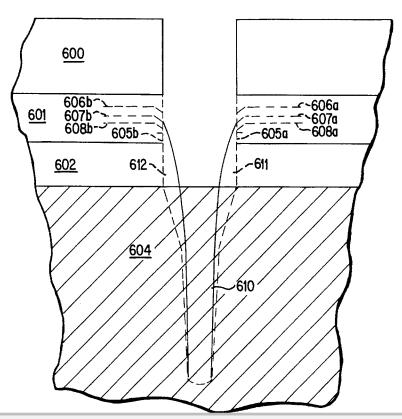
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Primary Examiner—William Powell Attorney, Agent, or Firm—Banner & Witcoff, Ltd.

[57] ABSTRACT

In a method of etch profile shaping through wafer temperature control during an etch process wherein deposition of a passivation film is temperature dependent, a gap between a semiconductor wafer to be etched and a cathode is pressurized at a first pressure, and the pressure in the gap is changed to a second pressure at a predetermined time during the etch process, thereby altering heat transfer from the semiconductor wafer to the cathode. The temperature of the wafer is adjusted one or more times during an etching process to control profile shaping of deep trenches, contact holes and shapes for mask opening shaping during the etch process.

26 Claims, 8 Drawing Sheets





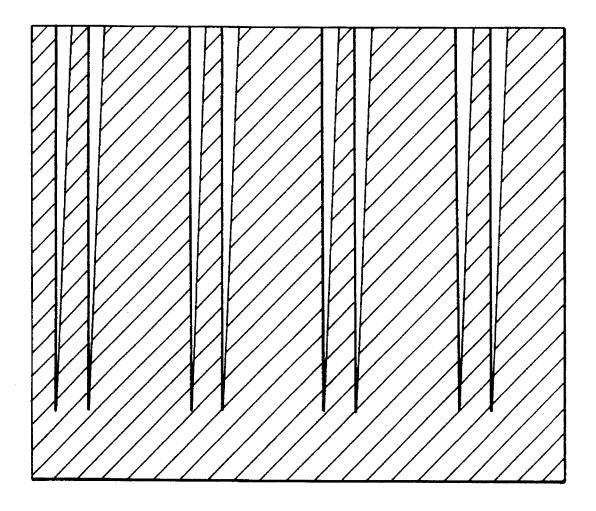


FIG.1

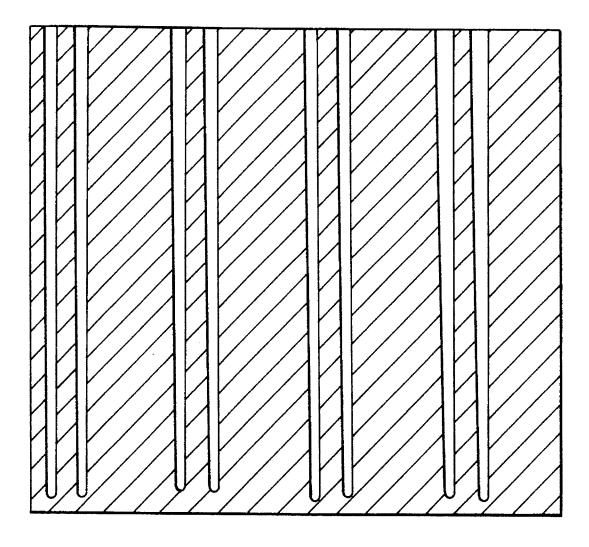
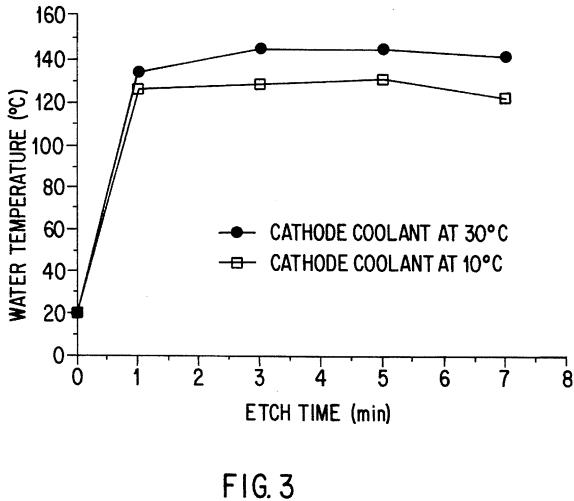
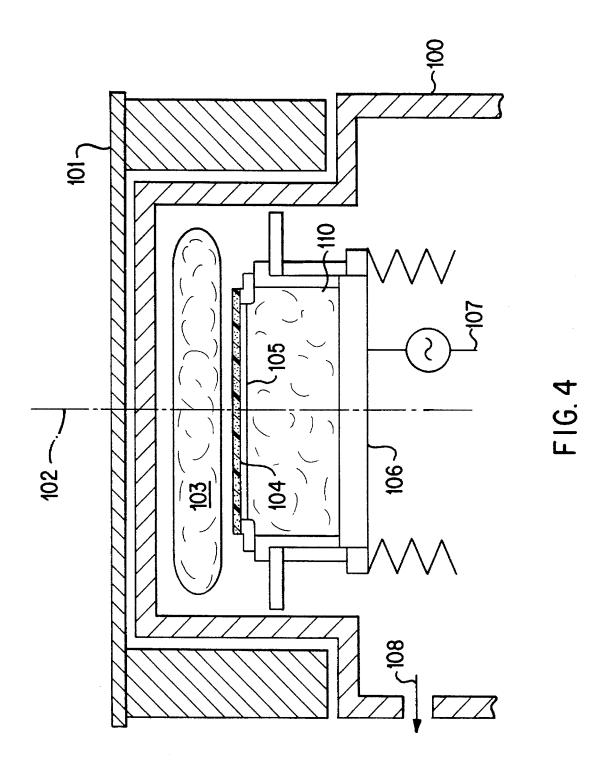


FIG. 2









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